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(54) **Title:** GAS INTAKE SYSTEM FOR SEMICONDUCTOR PROCESS DEVICE, SEMICONDUCTOR PROCESS DEVICE, AND GAS INTAKE METHOD

(54) 发明名称: 半导体工艺设备的进气系统、半导体工艺设备及进气方法

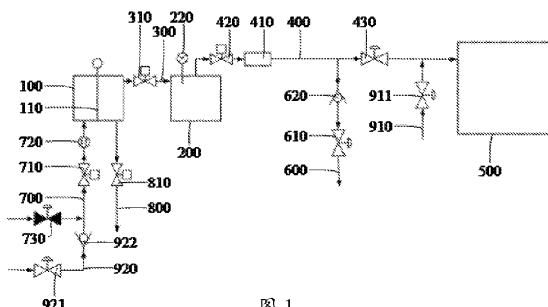


图 1

(57) **Abstract:** The present application relates to the technical field of semiconductors, and in particular, to a gas intake system for a semiconductor process device, a semiconductor process device, and a gas intake method. The gas intake system comprises a water storage tank, a gas storage tank, a steam conveying pipe, and a gas supply pipe. The water storage tank is provided with a water inlet port capable of being opened and closed, and a first heating device is arranged on the water storage tank. Two ends of the steam conveying pipe are connected to a gas outlet of the water storage tank and a gas inlet of the gas storage tank, respectively. The gas storage tank can be connected to or disconnected from a process chamber of the semiconductor process device by means of the gas supply pipe. When one of the water inlet port and the steam conveying pipe is in an opened state, the other is in a closed state. The present application can improve the intake stability of steam.

(57) 摘要: 本申请属于半导体技术领域, 具体涉及一种半导体工艺设备的进气系统、半导体工艺设备及进气方法。该进气系统包括储水箱、储气箱、水蒸气输送管路和供气管路, 储水箱具有可通断的进水接口, 且储水箱上设有第一加热装置, 水蒸气输送管路的两端分别与储水箱的出口和储气箱的进口相连接, 储气箱通过供气管路与半导体工艺设备的工艺腔室可通断地连通, 在进水接口和水蒸气输送管路中的一者处于导通状态的情况下, 另一者处于截止状态。本申请能够提升水蒸气的进气稳定性。

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SE, SG, SK, SL, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ,
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